Accepted Manuscript

Regular article

2.5-µm InGaAs photodiodes grown on GaAs substrates by interfacial misfit array technique

Pamela Jurczak, Kimberly A. Sablon, Marina Gutiérrez, Huiyun Liu, Jiang Wu

PII: S1350-4495(16)30684-3

DOI: http://dx.doi.org/10.1016/j.infrared.2017.02.001

Reference: INFPHY 2231

To appear in: Infrared Physics & Technology

Received Date: 30 November 2016 Revised Date: 1 February 2017 Accepted Date: 3 February 2017



Please cite this article as: P. Jurczak, K.A. Sablon, M. Gutiérrez, H. Liu, J. Wu, 2.5-µm InGaAs photodiodes grown on GaAs substrates by interfacial misfit array technique, *Infrared Physics & Technology* (2017), doi: http://dx.doi.org/10.1016/j.infrared.2017.02.001

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

CCEPTED MANUSCRIPT

2.5-µm InGaAs photodiodes grown on GaAs substrates by interfacial misfit array technique

Pamela Jurczak¹, Kimberly A. Sablon², Marina Gutiérrez³, Huiyun Liu¹, and Jiang Wu^{1,*}

¹ Department of Electronic and Electrical Engineering, University College London, Torrington

Place, London, WC1E 7JE, United Kingdom

² United States Army Research Laboratory, 2800 Powder Mill Road, Adelphi, Maryland 20783-

1197, United States of America

³ Department of Material Science and Metallurgic Engineering, The University of Cadiz, 11510,

Puerto Real, Cadiz, Spain

*Email: jiang.wu@ucl.ac.uk

Abstract

In_{0.85}Ga_{0.15}As photodetectors grown on GaAs substrates using an interfacial misfit

array-based simple buffer are studied. The material quality is assessed with a range of

characterization tools showing low surface roughness and low density of threading

dislocations. These results indicate a significant improvement on crystal quality compared to

structures grown on InP substrates by using metamorphic buffers. Quantum efficiency and

responsivity measurements show good performance of the fabricated devices between 1.5

and 2.5 µm, making them highly suitable for short-wavelength infrared applications.

Keywords: infrared; photodiodes; epitaxy; interfacial misfit array; short-wavelength

Introduction

InGaAs short-wavelength infrared (SWIR) detectors are widely used in space remote sensing,

environment monitoring, night vision, spectroscopy, etc. [1]. The In_{0.53}Ga_{0.47}As photodetectors

lattice-matched to InP substrate have a limited cut-off wavelength of 1.7 µm. Among many of

these applications, e.g. gas sensing, it is highly desirable to extend the cut-off wavelength

beyond 2.5 µm. To meet such a goal, the indium content in In_xGa_{1-x}As must be increased to

80%~85%, which results in a large lattice mismatch (+1.85% ~ +2.2%) between the InGaAs

Download English Version:

https://daneshyari.com/en/article/5488708

Download Persian Version:

https://daneshyari.com/article/5488708

<u>Daneshyari.com</u>